

TRADEMARK ASSIGNMENT

Electronic Version v1.1
 Stylesheet Version v1.1

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	Release of Security Interest in Trademarks

CONVEYING PARTY DATA

Name	Formerly	Execution Date	Entity Type
ORIX Venture Finance LLC		07/05/2006	LIMITED LIABILITY COMPANY:

RECEIVING PARTY DATA

Name:	Goldfinger Technologies, LLC
Street Address:	6330 Hedgewood Drive
Internal Address:	#150
City:	Allentown
State/Country:	PENNSYLVANIA
Postal Code:	18106
Entity Type:	LIMITED LIABILITY COMPANY: DELAWARE

Name:	Akrion Inc.
Street Address:	6330 Hedgewood Drive
Internal Address:	#150
City:	Allentown
State/Country:	PENNSYLVANIA
Postal Code:	18106
Entity Type:	CORPORATION: DELAWARE

PROPERTY NUMBERS Total: 8

Property Type	Number	Word Mark
Registration Number:	2691082	AKRION
Registration Number:	2295797	GOLDFINGER
Registration Number:	2993100	LUCID2
Registration Number:	1598327	SUBMICRON
Registration Number:	1574491	SUNBURST
Registration Number:	2604390	V

CH \$215.00 2691082

Registration Number:	2655977	V VERTEQ
Registration Number:	2040148	VERTEQ

CORRESPONDENCE DATA

Fax Number: (215)832-5347
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Correspondent Name: Zachary A. Aria
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ATTORNEY DOCKET NUMBER:	121529-00100
NAME OF SUBMITTER:	Zachary A. Aria
Signature:	/Zachary A. Aria/
Date:	08/18/2006


Total Attachments: 13
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RELEASE OF SECURITY INTEREST IN PATENTS AND TRADEMARKS

For good and valuable consideration, the receipt and sufficiency of which is hereby acknowledged, and intending to be legally bound hereby, **ORIX Venture Finance LLC**, a limited liability company, with an office located at 1177 Avenue of the Americas, 10th Floor, New York, NY 10036 ("Exiting Lender"), hereby terminates and releases the security interest it has or may have in and to (i) the trademarks (including any registration thereof) identified on Schedule A annexed hereto and made part hereof, (ii) the patents and patent applications (including any continuation, divisional, reissue, reexamination, extensions and/or registration thereof) identified on Schedule B annexed hereto and made part hereof (collectively, the "Intellectual Property"), which are the subject of a security interest pursuant to that certain (x) Intellectual Property and Security Agreement dated as of April 28, 2004, executed by **Goldfinger Technologies, LLC**, a Delaware limited liability company ("Goldfinger"), with an office located at 6330 Hedgewood Dr., #150, Allentown, PA 18106 and Exiting Lender, which was recorded with the United States Patent and Trademark Office or (y) the Loan and Security Agreement dated as of April 28, 2004, executed by Exiting Lender and **Akrion Inc.**, a Delaware corporation ("Akrion"), with an office located at 6330 Hedgewood Dr., #150, Allentown, PA 18106, as the case may be (the foregoing termination and release are referred to herein as, the "Release in Security Interest"). For the avoidance of doubt, Exiting Lender also terminates and releases the security interest it has or may have in all Intellectual Property acquired by any predecessors or successors of Goldfinger and Akrion including without limitation "Akrion Technologies, Inc.," "Verteq, Inc." and "Akrion, LLC."

Dated: July 5, 2006

ORIX VENTURE FINANCE LLC

By: 
Name: Kevin P. Sheehan
Title: President & CEO

SCHEDULE A

TRADEMARKS

(See Attached)

SCHEDULE A

MARK	REGISTRATION NO.	COUNTRY
AKRION	608,876	Canada
AKRION	2,894,970	CTM
AKRION	4,404,040	Japan
AKRION	4,688,464	Japan
AKRION	MA/1323/99	Malaysia
AKRION	T99/01516f	Singapore
AKRION	T02/16311D	Singapore
AKRION	476,864	South Korea
AKRION	566,614	South Korea
AKRION	922,154	Taiwan
AKRION	1,085,189	Taiwan
AKRION	2,691,082	United States
AKRION (IN SIMPLIFIED CHINESE CHARACTERS)	1,098,920	Taiwan
G300	T03/145,56Z	Singapore
GOLDFINGER	1,100,908	CTM
GOLDFINGER	4,519,693	Japan
GOLDFINGER	468,120	South Korea
GOLDFINGER	2,295,797	United States
LUCID2	3,715,221	China
LUCID2	4,749,321	Japan
LUCID2	T03/143557H	Singapore
LUCID2	1,115,142	Taiwan
LUCID2	2,993,100	United States
SUBMICRON	805,669	Taiwan
SUBMICRON	1,598,327	United States
SUNBURST	1,169,488	Germany

MARK	REGISTRATION NO.	COUNTRY
SUNBURST	1,574,491	United States
V (Stylized)	2,604,390	United States
V VERTEQ (Stylized)	2,655,977	United States
VCS	4,272,764	Japan
VERTEQ	4,406,459	Japan
VERTEQ	2,040,148	United States

SCHEDULE B

PATENTS

(See Attached)

AKRION PATENT SCHEDULE

Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
VERTE.003A	Cleaning Apparatus	US	07/043,852	29-Apr-87	4,804,007	14-Feb-89	Akron Technologies, Inc.
VERTE.003B	Megasonic Cleaning Apparatus	US	07/043,862	15-Jan-88	4,869,278	26-Sep-89	Akron Technologies, Inc.
VERTE.003E	Megasonic Cleaning Apparatus	US	07/272,501	16-Nov-88	4,998,549	12-Mar-91	Akron Technologies, Inc.
VERTE.003C1	Megasonic Cleaning Apparatus	US	07/482,086	15-Feb-90	5,037,481	6-Aug-91	Akron Technologies, Inc.
VERTE.007A	Apparatus for treating wafers utilizing megasonic energy	US	07/197,867	24-May-88	4,854,337	8-Aug-89	Akron Technologies, Inc.
VERTE.009A	Single Wafer Megasonic Semiconductor Wafer Processing System Apparatus	US	07/598,426	16-Oct-90	5,090,432	25-Feb-92	Akron Technologies, Inc.
VERTE.009DV1	Single Wafer Megasonic Semiconductor Wafer Processing System	US	07/809,799	18-Dec-91	5,286,657	15-Feb-94	Akron Technologies, Inc.
VERTE.010A	Single Chamber Megasonic Energy Cleaner	US	07/598,909	16-Oct-90	5,148,823	22-Sep-92	Akron Technologies, Inc.
VERTE.023A	Semi-conductor Wafer Processing Apparatus	US	08/042,889	5-Apr-93	5,365,960	22-Nov-94	Akron Technologies, Inc.
VERTE.024RX	Re-examination of US Pat 4,869,278 - Megasonic Cleaning Apparatus	US	90/002,852	2-Oct-92	4,869,278	26-Sep-89	Akron Technologies, Inc.
VERTE.025RX	Re-examination of US Pat 4,998,549	US	90/002,851	2-Oct-92	4,998,549	12-Mar-91	Akron Technologies, Inc.
VERTE.026RX	Re-exam of US Pat 5,037,481 - Megasonic Cleaning Method	US	90/002,853	2-Oct-93	5,037,481	6-Aug-91	Akron Technologies, Inc.
VERTE.027CP1	Semiconductor Wafer Cleaning System	US	08/361,139	12-Dec-94	5,656,097	12-Aug-97	Akron Technologies, Inc.
VERTE.027CP2	Semiconductor Wafer Cleaning System	US	08/910,033	11-Aug-97	5,950,645	14-Sep-99	Akron Technologies, Inc.
VERTE.027CP2D	Semiconductor Wafer Cleaning System	US	09/358,568	20-Jul-99	6,158,445	12-Dec-00	Akron Technologies, Inc.
VERTE.027CP2DC	Semiconductor Wafer Cleaning System	US	09/694,938	23-Oct-00	6,378,534	20-Apr-02	Akron Technologies, Inc.
VERTE.027DV2	Semiconductor Wafer Cleaning System	US	08/908,330	7-Aug-97	5,908,509	11-Jun-99	Akron Technologies, Inc.
VERTE.027DV3	Semiconductor Wafer Cleaning System	US	08/908,345	7-Aug-97	5,996,595	12-Dec-99	Akron Technologies, Inc.
VERTE.-29A	Method and Apparatus for Drying Semiconductor Wafers	US	08/275,807	15-Jul-94	5,556,479	17-Nov-96	Akron Technologies, Inc.

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Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
VERTE.032A	Wafer Cleaning System	US	08/724,518	20-Sep-96	6,039,059	21-Mar-00	Aktron Technologies, Inc.
VERTE.032CP1	Wafer Cleaning System	US	09/57,182	8-Apr-98	6,140,744	31-Oct-00	Aktron Technologies, Inc.
VERTE.032CPC1	Wafer Cleaning Method	US	09/643,328	22-Aug-00	6,295,999	2-Oct-01	Aktron Technologies, Inc.
VERTE.032CPC1C1	Wafer Cleaning System	US	09/953,504	13-Sep-01	6,463,938	15-Oct-02	Aktron Technologies, Inc.
VERTE.032CPCCC1	Wafer Cleaning Method	US	10/243,463	12-Sep-02	6,681,782	27-Jan-04	Aktron Technologies, Inc.
VERTE.032CPCCC1D	Wafer Cleaning System	US	10/726,774	3-Dec-03			Goldfinger Technologies, LLC
VERTE.032CPCCC2	Wafer Cleaning System	US	10/243,486	12-Sep-02	6,684,891	3-Feb-04	Aktron Technologies, Inc.
VERTE.032B	Transducer Assembly for Megasonic Processing of an Article	US	11/375907	15-Mar-06			NOT RECORDED YET
VERTE.032C	Transducer Assembly for Megasonic Processing of an Article	US	11/386,634	22-Mar-06			NOT RECORDED YET
VERTE.032VBE	Wafer Cleaning System	Belgium	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VDE	Wafer Cleaning System	Germany	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VFR	Wafer Cleaning System	France	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VGB	Wafer Cleaning System	Great Britain	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VIT	Wafer Cleaning System	Italy	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VJP	Wafer Cleaning System	Japan	516502/1988	8-Sep-97	3493492	21-Nov-03	Verteq
VERTE.032VKR	Wafer Cleaning System	Korea	99-7002749	8-Sep-97	392242	9-Jul-03	Aktron Technologies, Inc.
VERTE.032VNL	Wafer Cleaning System	Netherlands	9793309.3	8-Sep-97	938745	20-Mar-02	Verteq
VERTE.032VRKR	Wafer Cleaning System	Korea	102002701/11609	8-Jul-97	392243	9-Jul-03	Aktron Technologies, Inc.
VERTE.051A	Gas Seal and Support for Rotating Semiconductor Processor	US	09/040,176	17-Mar-98	6,125,551	3-Oct-00	Aktron Technologies, Inc.
VERTE.075A	Megasonic Probe Energy Attenuators	US	09/922,509	3-Aug-01	6,679,272	20-Jan-04	Aktron Technologies, Inc.
VERTE.075C1	Apparatus and Method for Reducing Damage to Substrates During Megasonic Cleaning	US	10/760,596	20-Jan-04	6,892,738	17-May-05	Aktron Technologies, Inc.
VERTE.076A	Megasonic Probe Energy Director	US	10/059,682	29-Jan-02			Aktron Technologies, Inc.
VERTE.076-501	Megasonic Probe Energy Director	EPO	3703722.3	29-Jul-04			Goldfinger Technologies, LLC
VERTE.076-502	Megasonic Probe Energy Director	Japan	2003-563743	29-Jul-04			Goldfinger Technologies, LLC

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Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
VERTE.076-503	Megasonic Probe Energy Director	Korea	2004-7011627	28-Jul-04			Goldfinger Technologies, LLC
VERTE.076-504	Megasonic Probe Energy Director	Singapore	200404177.8	25-Mar-04			Goldfinger Technologies, LLC
VERTE.076-505	Megasonic Probe Energy Director	China	3805097.8	24-Sep-04			Goldfinger Technologies, LLC
VERTE.077A	Reciprocating Megasonic Probe	US	10/140,029	6-May-02			Aktron Technologies, Inc.
VERTE.079A	Megasonic Cleaning System with Buffered Cavitation Method	US	10/341,425	10-Jan-03			Aktron Technologies, Inc.
VERTE.080A	Megasonic Cleaner and Dryer System	US	10/171,426	12-Jun-02	6,754,980	29-Jun-04	Aktron Technologies, Inc.
VERTE.080-101	Megasonic Cleaner and Dryer System	US	10/864,927	10-Jun-04			Goldfinger Technologies, LLC.
VERTE.080-102	Megasonic Cleaner and Dryer System	US	10/865,440	10-Jun-04			Goldfinger Technologies, LLC.
VERTE.080VJP	Megasonic Cleaner and Dryer System	Japan	2003-516088	12-Jun-02			Goldfinger Technologies, LLC
VERTE.080VEP	Megasonic Cleaner and Dryer System	Europe	2742054.6	12-Jun-02			Verteq
VERTE.080VKR	Megasonic Cleaner and Dryer System	Korea	10-2003-7016342	12-Jun-02			Verteq
VERTE.081A	Megasonic Cleaner Probe System with Gasified Fluid	US	09/906,384	16-Jul-01	6,684,890	3-Feb-04	Aktron Technologies, Inc.
VERTE.081C1	Sonic-Energy Cleaner System with Gasified Fluid	US	10/742,214	19-Dec-03	7,047,989	23-May-06	Aktron Technologies, Inc.
VERTE.0081-102PCT	Megasonic Processing System with Gasified Fluid	PCT	PCT/US2005/031349	1-Sep-05			Goldfinger Technologies, LLC
VERTE.084A	Method of Applying Liquid to a Megasonic Apparatus for Improved Cleaning Control	US	10/171,431	12-Jun-02			Aktron Technologies, Inc.
VERTE.085A	Stackable Process Chambers	US	10/171,429	12-Jun-02	6,923,192	2-Aug-05	Aktron Technologies, Inc.
VERTE.086A	Megasonic Cleaner and Dryer System		10/171,494	12-Jun-02			Aktron Technologies, Inc.
VERTE.088A	Megasonic Cleaner and Dryer System	US	10/171,430	12-Jun-02	6,928,751	16-Aug-05	Aktron Technologies, Inc.
VERTE-0100-100	Megasonic Cleaning Using Supersaturated Cleaning Solution	US	10/864,929	10-Jun-04			Aktron Technologies, Inc.
VERTE-0100-501	Megasonic Cleaning Using Supersaturated Cleaning Solution Liquid	Taiwan	93116958	10-Jun-05			Goldfinger Technologies, LLC

Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
VERTE-0100-500CN	Megasonic Cleaning Using Supersaturated Cleaning Solution Liquid	China	200480020523.70	12-Dec-05			Aktron Technologies, Inc.
VERTE-0100-500JP	Megasonic Cleaning Using Supersaturated Cleaning Solution Liquid	Japan	not yet available	12-Dec-05			Goldfinger Technologies, Inc.
VERTE-0100.500EP	Megasonic Cleaning Using Supersaturated Cleaning Solution Liquid	Europe	04 776 442.8	12-Dec-05			Goldfinger Technologies, LLC.
VERTE-0100-500KR	Megasonic Cleaning Using Supersaturated Cleaning Solution Process for Etching Oxide Films	Korea	2005-7023902	12-Dec-05			Goldfinger Technologies, LLC
108430.001	Process for Etching Oxide Films	US	08/851,668	6-May-97	5,807,408	15-Sep-98	Aktron Technologies, Inc.
108430.002	Process for Etching Oxide Films	US	07/876,043	30-Apr-92	5,234,540	28-Jun-94	Aktron Technologies, Inc.
108430.005	Megasonic Cleaning System	US	08/277,792	20-Jul-94	5,625,249	29-Apr-97	Aktron Technologies, Inc.
108430.005A	Megasonic Cleaning System	US	07/791,094	12-Nov-91	5,247,954	28-Sep-93	Aktron Technologies, Inc.
108430.014A	Surface Particle Barrier	US	10/014,121	11-Dec-01	6,732,749	11-May-04	Aktron Technologies, Inc.
108430.016A	Drying Vapor Generation	US	10/098,847	15-Mar-02	6,722,056	20-Apr-04	Aktron Technologies, Inc.
108430.016 JP	Drying Vapor Generation	Japan	2002-574701	15-Mar-02			Aktron LLC
108430.016EP	Drying Vapor Generation	Europe	273132.3	15-Mar-02			Aktron LLC
108430.016KR	Drying Vapor Generation	South Korea	10-2003-7012039	14-Feb-04			Aktron LLC
108430.018A	Process Tank with Pressurized Mist Generation Pressurized Mist Generation	US	10/117,768	5-Apr-02	6,532,974	18-Mar-03	Aktron Technologies, Inc.
108430.018D	Process Tank with Pressurized Mist Generation	US	10/304,583	29-Nov-02	6,626,189	30-Sep-03	Aktron Technologies, Inc.
108430.018EP	Process Tank with Pressurized Mist Generation	EP	2764002.8	8-Apr-02			Aktron LLC
108430.018JP	Process Tank with Pressurized Mist Generation	Japan	2002-579135	8-Apr-02			Aktron LLC
108430.018KR	Process Tank with Pressurized Mist Generation	Korea	2003-7013102	8-Apr-02			Aktron LLC
108430.019A	Method and System for Chemical Injection in Silicon Wafer Processing	US	10/053,364	18-Jan-02	6,767,877	27-Jul-04	Aktron Technologies, Inc.
108430.020A	Nextgen Wet Process Tank	US	10/117,778	5-Apr-02	6,840,250	11-Jan-05	Aktron Technologies, Inc.

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Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
108430.021A	Chemical Concentration Control Device	US	10/117,725	5-Apr-02	6,766,818	27-Jul-04	Aktron Technologies, Inc.
108430.022A	Membrane Dryer	US	10/117,739	5-Apr-02	6,842,998	18-Jan-05	Aktron Technologies, Inc.
108430.022D	Membrane Dryer	US	10/951,009	27-Sep-04	6,928,750	12-Aug-05	Aktron Technologies, Inc.
108430.023A	Low Profile Wafer Carrier	US	10/053,449	17-Jan-02	6,871,657	29-Mar-05	Aktron Technologies, Inc.
108430.024CIP	Process and Apparatus for Removal of Photoresist from Semiconductor Wafers	US	10/366/054	13-Feb-03	6,818,563	16-Nov-04	Aktron Technologies, Inc.
108430.025	Process and Apparatus for Removing Photoresist Using Sparger	US	10/052,823	17-Jan-02	6,649,018	18-Nov-03	Aktron Technologies, Inc.
108430.025D	Method for Removal of Photoresist Using Sparger	US	10/634,440	5-Aug-03	6,863,836	8-Mar-05	Aktron Technologies, Inc.
108430.030B	Cleaning and Drying Method and Apparatus	US	10/091,011	4-Mar-02	6,837,944	4-Jan-05	Aktron Technologies, Inc.
108430.035A	Substrate Process Tank with Acoustical Source Transmission and Method of Processing Substrates	US	10/699,042		6,955,727	18-Oct-05	Aktron Technologies, Inc.
108430.035EP	Substrate Process Tank with Acoustical Source Transmission and Method of Processing Substrates	Europe	3778012.9	10-Oct-03			Aktron LLC
108430.035KR	Substrate Process Tank with Acoustical Source Transmission and Method of Processing Substrates	Korea	10-2005-7007603	29-Apr-05			Aktron LLC
108430.035CN	Substrate Process Tank with Acoustical Source Transmission and Method of Processing Substrates	China	200380107761.70				Aktron LLC
108430.036B	Capillary Drying of Substrates	US	10/358,636	5-Feb-03	6,907,890	21-Jun-05	Aktron Technologies, Inc.
108430.036CN	Capillary Drying of Substrates	China	3805652.6	9-Sep-04			Aktron LLC
108430.036EP	Capillary Drying of Substrates	EPO					Aktron LLC
108430.036JP	Capillary Drying of Substrates	Japan	2003-565662				Aktron LLC
108430.036KR	Capillary Drying of Substrates	Korea	2004-7012117	5-Aug-04			Aktron LLC
108430.365G	Capillary Drying of Substrates	Singapore	200404652-0	5-Feb-03			Aktron LLC
108430.037A	System and Method for Point-of-Use Filtration and Purification of Fluids Used in Substrate Processing	US	10/895,511	20-Jul-04			Aktron Technologies, Inc.
108430.038A	Process Sequence for Photoresist and/or Cleaning of Photomasks for Integrated Circuit Manufacturing	US	10/909,764	2-Aug-04			NOT RECORDED YET

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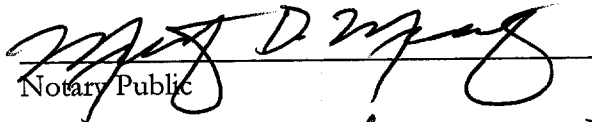
Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
1008430.038TW	Process Sequence for Photoresist and/or Cleaning of Photomasks for Integrated Circuit Manufacturing	Taiwan	93123002	30-Jul-04			Aktron LLC
108430.038EP	Process for Photoresist Stripping and/or Cleaning of Photomasks for Integrated Circuit Manufacturing	Europe	4779750.1				Aktron, LLC
108430.039A	Reticle Cleaning Carrier	US	10/931,441	5-Sep-04			NOT RECORDED YET
108430.039PCT	Reticle Cleaning Carrier	PCT	PCT/US0428447	1-Sep-04			Aktron LLC
108430.039TW	Reticle Cleaning Carrier	Taiwan	9126709	1-Sep-04			Aktron, Inc.
108430.040PCT	System and Method for Selective etching of Silicon Nitride During Substrate Processing	PCT	PCT/2004/043887	30-Dec-04			
108430.041A	System and Method of Powering a Sonic Energy Source and Use of the Same to Process Substrates	US	11/227,705	15-Sep-05			Aktron Technologies, Inc.
108430.041PCT	System and Method of Powering a Sonic Energy Source and Use of the Same to Process Substrates	PCT	PCT/US2005/033023	15-Sep-05			
108430.041TW	System and Method of Powering a Sonic Energy Source and Use of the Same to Process Substrates	Taiwan	94131851	15-Sep-05			Aktron, Inc.
108430.042A	Reduced Pressure UV 172 Radiation	US	11/178,923	11-Jul-05			NOT RECORDED YET
108430.042PCT	Reduced Pressure UV 172 Radiation	PCT	PCT/US2005/024510	8-Jul-05			Aktron LLC
108430.043A	Method and Apparatus for Creating Ozonated Process Solutions Having High Ozone Concentration	US	11/177,147	8-Jul-05			NOT RECORDED YET
108430.043PCT	Method and Apparatus for Creating Ozonated Process Solutions Having High Ozone Concentration		PCT/US2005/024509	8-Jul-05			
108430.044A	Pre-Gate Cleaning Method using DIO#	US	11/176,406	7-Jul-05			Aktron LLC
108430.044PCT	Pre-Gate Cleaning Method using DIO#		PCT/US2005/024030	7-Jul-05			NOT RECORDED YET
108430.045A	Apparatus and Method for Removing Trace Amounts of Liquid from Substrates dueing single substrate processing	US	11/266402	3-Nov-05			NOT RECORDED YET
108430.045PCT	Apparatus and Method for Removing Trace Amounts of Liquid from Substrates dueing single substrate processing	PCT	PCT/US2005/040251	3-Nov-05			Aktron, Inc.

Docket Number	Title	Country	Application Number	Application Date	Patent Number	Issue Date	Registered Owner
108430.047A	System and Method of Cleaning Substrates with Sonic Energy that Reduces or Eliminates Damage to Semi-Conductor Devices	US	11/370,361	8-Mar-06			NOT RECORDED YET
108430.047B	System and Method of Cleaning Substrates with Sonic Energy that Reduces or Eliminates Damage to Semi-Conductor Devices	US	11/370,707	8-Mar-06			NOT RECORDED YET
108430.047TW	System and Method of Cleaning Substrates with Sonic Energy that Reduces or Eliminates Damage to Semi-Conductor Devices	Taiwan	95107855	8-Mar-06			
108430.047PCT	System and Method of Cleaning Substrates with Sonic Energy that Reduces or Eliminates Damage to Semi-Conductor Devices	PCT	PCTUS06/08452	8-Mar-06			Aktron, Inc.
108430.048	System and Method of Cleaning Substrates using high frequency megasonics and or Cavitation Control	US	60/690,586	15-Jun-05			NOT RECORDED YET
108430.049	System and Method of Processing Substrates Using a Sub-Ambient Process solution and Sonic Energy	US	60/724,495	7-Oct-05			Aktron Technologies, Inc.
108430.051	Backside Cleaning	US	60/760,820	20-Jan-06			Aktron Technologies, Inc.
108430.053	System and Method for Drying a Rotating Substrate	US	60/759,948	18-Jan-06			Aktron Technologies, Inc.
108430.054	Spray Jet with CO2	US	60/798,831	8-May-06			NOT RECORDED YET
108430.054P2	Spray Jet Cleaning Apparatus and Method	US	Not Available Yet	25-May-06			NOT RECORDED YET
108430.055	Megasonic transducer assembly having direct bonded non-reactive plastic transmitter	US	60/762,827	26-Jan-06			Aktron Technologies, Inc.
108430.061	Hydrophobic dryer	US	60/8809,656	30-May-06			NOT RECORDED YET

CORPORATE ACKNOWLEDGMENT

STATE OF [NEW YORK])
) ss.:
COUNTY OF [NEW YORK])

On this 11th day of July, 2006, Kevin Sheehan personally appeared before me and being duly sworn, declared that s/he is the President and CEO of ORIX Venture Finance LLC, that s/he signed the foregoing Release of Security Interest in the Intellectual Property in the capacity designated, and that he has read the Release of Security Interest in the Intellectual Property, and the statements contained therein are true.


Notary Public

My Commission Expires: 6-19-2010

MISTY D. MARRIS
Notary Public, State of New York
No. 01MA6147935
Qualified in Nassau County
Commission Expires June 19, 2010